L Number	Hits	Search Text	DB	Time stamp
-	59	(tungsten adj silicide) and DCS and "WF.sub.6" and silane	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/16 13:27
-	100946	film near2 (depositing or deposited or deposition or deposit)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/16 13:29
-	2071	(film near2 (depositing or deposited or deposition or deposit)) and (reaction adj gas)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/16 13:29
-	1303	((film near2 (depositing or deposited or deposition or deposit)) and (reaction adj gas)) and plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/16 13:30
-	686	(((film near2 (depositing or deposited or deposition or deposit)) and (reaction adj gas)) and plasma) and ("SiH.sub.4" or silane or "SiF.sub.4" or TEOS)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/16 14:12
-	176	((((film near2 (depositing or deposited or deposition or deposit)) and (reaction adj gas)) and plasma) and ("SiH.sub.4" or silane or "SiF.sub.4" or TEOS)) and (("SiH.sub.4" or silane or "SiF.sub.4" or TEOS) near4 (reaction adj gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/16 14:14
-	0	(((((film near2 (depositing or deposited or deposition or deposit)) and (reaction adj gas)) and plasma) and ("SiH.sub.4" or silane or "SiF.sub.4" or TEOS)) and (("SiH.sub.4" or silane or "SiF.sub.4" or TEOS) near4 (reaction adj gas))) and (initial adj film)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/16 14:15
-	0	((((((film near2 (depositing or deposited or deposition or deposit)) and (reaction adj gas)) and plasma) and ("SiH.sub.4" or silane or "SiF.sub.4" or TEOS)) and (("SiH.sub.4" or silane or "SiF.sub.4" or TEOS) near4 (reaction adj gas))) and (initial adj film)) and (flow adj rate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/16 14:16
-	367	((((film near2 (depositing or deposited or deposition or deposit)) and (reaction adj gas)) and plasma) and ("SiH.sub.4" or silane or "SiF.sub.4" or TEOS)) and (flow adj rate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/16 14:16
-	112	(((((film near2 (depositing or deposited or deposition or deposit)) and (reaction adj gas)) and plasma) and ("SiH.sub.4" or silane or "SiF.sub.4" or TEOS)) and (("SiH.sub.4" or silane or "SiF.sub.4" or TEOS) near4 (reaction adj gas))) and (flow adj rate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/05/16 14:35

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